

# Semiconductor Microscope

## PSM-1000/PSM-1000E



PSM-1000



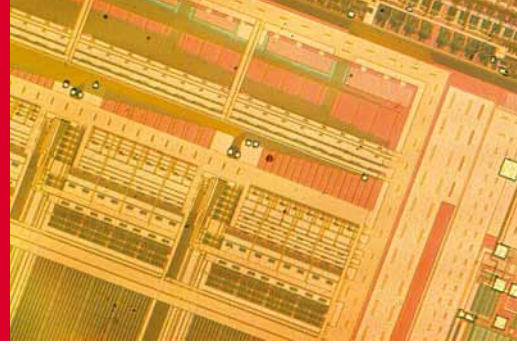
PSM-1000E

“All – In One” laser ready microscope for inspection, testing and corrections in the semiconductor industry.

Semiconductor

		PSM-1000	PSM-1000E
Trinocular tube	Image	Erect Image	
	Interpupillary distance	Siedentopf type, adjustment range: 55mm-75 mm	
	Field Number	24mm	
	Optical pass ratio	Switchable [eyepiece/laser = 100/0 or 0/100]; Simultaneous observation [50:50]	
	Observation angle adjustment	/	3° to 30°
Main unit	Tube lens [correction]	1x [ultraviolet and infrared] and 2x [visible]	
	Laser work	Pull out beam splitter for laser work	
	Applicable laser	1064/532/355nm NWR laser	
Magnification range	20X – 2000X		
Focus Adjustment	With coaxial coarse and fine focusing wheels [right/left] [50mm travel range, 0.1mm/rev. for fine adjustment, 4mm/rev. for coarse adjustment]		
Loading weight on optical tube	20.5kg		
Camera mount	C-mount adapter		
Light source [optional]	150W cold light source, light guide length 2m.		
Objective nosepiece	Parcenterable, outward, rotary type for bright field lens [with 4 mounts], detachable		
Objectives [optional]	ELWD Plan Apo	2x, 5x, 10x, 20x, 50x	
	ULWD Plan Apo	50x, 100x	
	ELWD Plan Apo [Parfocality Adjustable]	2x, 5x, 10x, 20x, 50x	
	ULWD Plan Apo [Parfocality Adjustable]	50x, 100x	
	NIR Apo	20x, 50x	
Mass [main unit/light source]	6.8kg/2.5kg		

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## APO Objective



Superb optics with long working distances for crisp, detailed, aberration-free images.

Lens optical character	Magnification	N.A.	W.D. (mm)	Resolution (um)
<b>ELWD Standard</b>	2x	0.055	34	5
	5x	0.14	34	2
	10x	0.28	33.5	1
	20x	0.42	20	0.7
	50x	0.55	13	0.5
	100x(HNA)	0.8	3	0.34
<b>ELWD Parfocality Adjustable</b>	2x	0.055	34	5
	5x	0.14	34	2
	10x	0.28	33.5	1
	20x	0.42	20	0.7
<b>ULWD Standard</b>	50x	0.42	20.5	0.7
	100x	0.55	13	0.5
<b>Plan NIR</b>	20x	0.4	20.5	0.7
	50x	0.42	19	0.7